



Wear-resistive and electrically conductive nitrogen-containing DLC film consisting of ultra-thin multilayers prepared by using filtered arc deposition

Toru Harigai^{1*}, Koki Tamekuni¹, Yushi Iijima¹, Satoshi Degai¹, Tsuyoshi Tanimoto¹, Yoshiyuki Suda¹, Hirofumi Takikawa¹, Shigeki Takago², Haruyuki Yasui², Satoru Kaneko³, Shinsuke Kunitsugu⁴, Hitoe Habuchi⁵, Masao Kamiya⁶, Makoto Taki⁷, and Hidenobu Gonda⁸

¹Toyohashi University of Technology, Toyohashi, Aichi 441-8580, Japan

²Industrial Research Institute of Ishikawa, Kanazawa, Ishikawa 920-8203, Japan

³Kanagawa Institute of Industrial Science and Technology, Ebina, Kanagawa 243-0435, Japan

⁴Industrial Technology Center of Okayama Prefecture, Okayama 701-1296, Japan

⁵National Institute of Technology, Gifu College, Motosu, Gifu 501-0495, Japan

⁶Itoh Optical Industrial Co., Ltd., Gamagori, Aichi 443-0041, Japan

⁷Onward Ceramic Coating Co., Ltd., Nomi, Ishikawa 929-0111, Japan

⁸OSG Coating Service Co., Ltd., Toyokawa, Aichi 441-1231, Japan

*E-mail: harigai@ee.tut.ac.jp

Received November 14, 2018; accepted March 13, 2019; published online May 24, 2019

Nitrogen-containing diamond-like carbon (N-DLC) multilayer films approximately 500 nm thick were fabricated on tungsten carbide substrates as surface protective films with high wear-resistive and conductive properties. Each layer thickness of the N-DLC multilayer films was approximately 10 nm, and the films were a periodic bilayer structure consisting of hard and soft N-DLC layers. Owing to the high abrasion resistance of the hard layer and the low aggressiveness and high adhesion of the soft layer, the multilayer films showed good polishing and wear resistances compared with the hard N-DLC monolayer film, and the electrical resistivity was about half. In the case of DLC multilayer films consisting of hard N-free DLC and N-DLC films, the decrease of each layer thickness leads to the reduction of the polishing resistance. From X-ray reflectivity analysis of ultra-thin N-free DLC films, it was indicated that the film density of an ultra-thin N-free DLC film is lower than that of a thick N-free DLC film. In the DLC multilayer film with thin N-free DLC layers, it is possible that the polishing resistance of the whole DLC film reduced because the hardness the N-free DLC layer was decreased due to the low film density of each N-free DLC layer. © 2019 The Japan Society of Applied Physics

1. Introduction

Electrically conductive hard-coating films are required as a protective film on the tip of a contact pin that is used in the electrical inspection process.¹⁻³ Gold plating, which is the surface protective film of commercial contact pins, has the oxidation prevention of a base metal and high electrical conductivity but poor wear resistance. Also, the protective films of the contact pin are required to have high adhesion resistance for suppressing adhesion of the solder to the tip of the pin during the inspection process.³

Diamond-like carbon (DLC) films are amorphous structures that have been widely used as protective-coating films because the films have superior properties such as high hardness, high wear resistance, and excellent adhesion resistance.⁴⁻⁷ It is thought that a DLC film has sp² and sp³ carbon bonding structures, and its electrical resistivity is high.⁸ The typical electrical resistivity of DLC films is known as 10⁶–10⁸ Ω cm.^{9,10} When nitrogen is contained in the DLC film, the electrical resistivity of the nitrogen-containing DLC (N-DLC) film dramatically decreases^{3,11-17} however the decrease of the electrical resistivity is dominated by the increase of the electron carrier with increasing of the sp² bonding structure rather than that owing to the nitrogen doping in the film. The increase of the sp² bonding structure in a DLC film leads to a decrease of mechanical hardness in the film.

Harder N-DLC films in the N-DLC films have been prepared by filtered arc deposition (FAD) methods.^{3,18-26} The FAD methods are vacuum arc deposition (VAD) methods equipping a filtering duct for removing fine particles called a droplet generated from a cathode.^{3,18} In the VAD method, an arc spot that is active at high temperature is

formed on a cathode, and the cathode material evaporates. A thin film is formed by the evaporated cathode material reaching a substrate. As the cathode evaporates, droplets are also generated from the cathode. The droplets mixed in the film significantly degrade the film properties such as flatness and hardness. In the FAD methods, the distance from a cathode to a substrate is long passing through a filtering duct, and the mixing of droplets into a film is prevented.

It has been reported that adhesion to a substrate and wear resistance improved by alternately stacking a hard film and a soft film consisting of a metal film and/or a DLC film.²⁷⁻³⁵ The hard film has high abrasion resistance, but cracks and peeling are caused by loads during abrasion. On the other hand, the soft film has inferior wear resistance compared with the hard film, but show good adhesion. A multilayer film stacked alternately a hard film and a soft film is suppressed delamination of the hard film by the high adhesion of the soft film during abrasion, and exhibits high wear resistance as the whole film.²⁹ In our previous study, the multilayer film consisting of N-free high-density DLC layers and N-DLC layers showed low electrical resistivity and excellent wear resistance.³⁵ 8-layer DLC film with a N-free high-density DLC film as the top layer was about half the electrical resistivity compared with the monolayer N-free high-density DLC film.

In this paper, the polishing and wear resistances of DLC multilayer films with lower electrical resistivity prepared by using a FAD method are presented. The DLC multilayer films consisting of two kinds of DLC layers had thinner thickness per layer compared with our previous study.³⁵ Multilayer films with low electrical resistivity were formed with only N-DLC. In addition, the effect of layer thickness on